

Atomistic modeling of the dissociation of a screw dislocation in silicon

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Abstract The nature of dislocations involved in the plastic deformation of semiconductors is different in high- and low-temperature domains. Experimental investigations have not allowed to discriminate between dissociation and nucleation as the main reason behind this transition. In this work, the mechanisms leading to the dissociation of a screw dislocation in silicon, determined by means of atomistic calculations, are described. It is shown that kink pair formation, followed by successive kink migrations, leads to the formation of two 30° partial dislocations from the screw dislocation core. These mechanisms are structurally very similar to those involved in the formation and migration of kinks in the case of a single 30° partial dislocation, because of the close resemblance between the screw and 30° dislocation cores. The calculated activation energy of the whole process is 2.14 eV, thus quite comparable to the energies involved in the propagation of partial dislocations. This shows that dissociation and nucleation processes are likely to be activated at similar temperature ranges.

Introduction

The mechanical properties of semiconductors with the cubic zinc-blende structure are relatively well known nowadays. At high temperatures, above the brittle to ductile temperature (BDT), these materials will plastically deform due to the motion of Shockley partial

dislocations [1]. Below BDT instead, fracture occurs by the propagation of cracks [2]. However, this general picture is appropriate for bulk materials, since it has been recently shown to be possible to obtain a ductile behavior below the bulk BDT when one or several characteristic dimensions were reduced. Such a size effect has been demonstrated in the case of semiconductor nanowires [3–6], which are extremely important systems for nanotechnology [7, 8]. Semiconductor nano- and micro-pillars [9–13], nanospheres [14, 15], and nanobridges [16] were also the focus of extensive investigations. It is found that in these systems the BDT could be lower than in bulk materials, a phenomenon that is probably related to the growing surface influence in small dimension systems. This opens the way to the ductile deformation of semiconductors at moderate temperatures, although stresses in the GPa scale are typically required to reach plasticity [17]. Because of the continuous search to improve efficiency by reducing dimensions, such stress levels can now be obtained in real semiconductor devices [18]. For future microelectronics and nanotechnology applications, it is then essential to better understand plastic deformations occurring at low temperatures and high stresses.

Aside nanoscale systems, it is also possible to investigate this regime in macroscale samples by either scratching and indenting the surface [19–21], or using a confining pressure [22–25]. The former technique allows for reaching very high stress in a localized region, while the latter prevents the opening of crack, thus shifting fracture to higher stress levels. Available data clearly revealed that dislocations occurring at low temperature and high stress are non-dissociated [26] and are likely to be different from dislocations activated in the high-temperature regime.

An intriguing yet still unanswered question concerns the transition between the high-temperature/low-stress and

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low-temperature/high-stress regimes. One possible explanation is the occurrence of core transformations between dislocations. Another possibility is that dislocations in the two regimes are nucleated in well-separated stress and temperature conditions. A decade ago, transmission electronic microscopy experiments by Asaoka et al. revealed that in silicon perfect dislocations, nucleated at low temperature and high stress, would dissociate at a temperature ranging between 673 and 973 K [19]. These experiments were confirmed by additional investigations [20]. However, a study by Rabier and Demelet leads to the opposite conclusion that no dislocation core transformation occurs for temperatures up to 958 K [27]. Recently, Li and Picu have tried to address this issue by means of molecular dynamics simulations [28], also in silicon. They showed that no core transformation would occur by annealing only, but requires a large and well-oriented stress.

In order to shed light on this fundamental issue, I have performed atomistic calculations to determine the energy barriers associated with the transformation of a non-dissociated screw dislocation into two 30° Shockley partial dislocations, in the case of silicon. The choices of silicon and of the screw dislocation allow for a straightforward comparison with the aforementioned studies.

Numerical simulations

Atomistic simulations were performed using interatomic interactions described by the environment-dependent interatomic potential (EDIP), which has been specifically developed for modeling defects in silicon [29]. This potential is considered reliable for determining dislocation core properties [30–32]. Bulk calculations yield a lattice parameter a_0 equal to 5.4305 Å and a cohesive energy of 4.65 eV, as well as elastic constants $C_{11} = 175$ GPa, $C_{12} = 62$ GPa, and $C_{44} = 71$ GPa. Quenched molecular dynamics calculations were performed to obtain stable low-energy structures for all considered configurations. In a second stage, the nudged elastic band (NEB) technique [33] was used to determine the minimum energy paths and the activation energies between successive stable states, with 20 replicas in all cases. For an accurate calculation of the saddle state, the climbing image algorithm was employed [34]. The latter forces the image with the highest energy to climb up along the elastic band, leading to convergence toward the highest saddle point. Both relaxation and NEB computations were performed using a home-made version of the molecular dynamics code XMD [35], including implementations of the NEB method and EDIP.

The calculations were performed using a supercell oriented along the usual axis for dislocation modeling, i.e.,

$\hat{x} = [1\bar{2}1]$, $\hat{y} = [111]$, and $\hat{z} = [10\bar{1}]$. The supercell includes 8400 atoms, with dimensions being $20 \times 42 \times 10$ (6.651 nm 6.584 nm \times 3.840 nm). A screw, a 30° partial, or a couple of 30° partial dislocations were introduced in the center of the supercell, with the dislocation line along the \hat{z} -axis, using displacements calculated with anisotropic elasticity theory [1] and the elastic constants calculated with EDIP. Periodic boundary conditions were applied along the \hat{z} -axis only, to model straight dislocations of infinite lengths. Along the \hat{x} - and \hat{y} -axis, surface boundary conditions were used, and atoms at the cell faces were kept at locations defined by the elasticity theory during simulations.

Screw and 30° partial dislocations

Thanks to numerous studies, there is a general consensus concerning the dislocations associated with the plastic deformation of silicon in the ductile regime, i.e., at temperatures greater than the BDT. In fact, plasticity occurs through the multiplication and expansion of hexagonal dislocation loops composed of 60° and screw segments, both lying along $\langle 110 \rangle$ directions and moving in the so-called “glide” set of $\{111\}$ planes [1, 36]. Both dislocations are dissociated into Shockley partials, the screw into two 30° and the 60° into one 30° and one 90°, as in FCC materials. These partial dislocations bound an intrinsic stacking fault of width 6–10 nm [37, 38]. The core of these dislocations has been extensively studied [39, 40]. The 30° partial dislocation core is reconstructed along the dislocation line, with a periodicity of $\sqrt{2}a_0$ [41]. For the 90° core, two configurations have been proposed [42, 43], their core energies being so close that it is likely that both dislocations could be present at finite temperatures [44].

At low temperatures, below the BDT, there are less certainties. On one hand, it is now commonly agreed that dislocations are non-dissociated in this regime, and glide in the so-called “shuffle” set of $\{111\}$ planes [26]. But on the other hand, those are found to be lying not only along $\langle 110 \rangle$ orientations, but also along unexpected $\langle 112 \rangle$ and $\langle 123 \rangle$ orientations [26, 45]. The cores of dislocations with these peculiar orientations have not been identified up to now. Nevertheless, more information is available regarding non-dissociated $\langle 110 \rangle$ dislocations. Hence, two possible stable core structures have been identified for the screw dislocation, depending on whether the dislocation core is located at the center of an hexagon (A, $\{111\}$ shuffle set, Fig. 1) or at a bond center (C, $\{111\}$ glide set, same figure) [26, 46]. In the latter case, the dislocation core, C_2 , is reconstructed along the dislocation line with the same periodicity than the 30° partial dislocation core. The

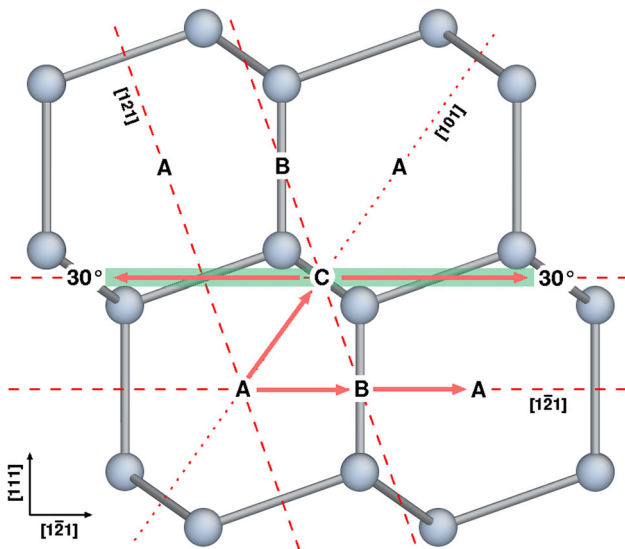


Fig. 1 Possible positions of a screw dislocation (A, B, and C) in the cubic diamond lattice, with the $\{111\}$ slip planes represented by thin dashed lines. The thick arrows show the dislocation core transformation path from A to C, followed by the dissociation in two 30° partial dislocations, which borders a stacking fault (green area) (Color figure online)

unreconstructed structure, C_1 , was found to be unstable [26]. First-principles calculations revealed that the A core is more mobile than the C_2 core [31, 47, 48], whereas the C_2 core is more stable [49, 50]. Note that another configuration corresponding to the location B is marked in Fig. 1. It has been shown to be a saddle point during screw dislocation displacement [51]. Another investigated case is the non-dissociated 60° dislocation core, which is assumed to be active for relaxing stresses in epitaxial thin films [52] or in loaded nanowires [53, 54]. It was predicted that only one core configuration could be involved in plastic deformation. However, this configuration exhibits a transient character, i.e., it becomes unstable at rest [55]. A different core structure is found to be energetically favored, albeit it was shown to be sessile in the allowed ranges of stress and temperature.

This overview of dislocations in silicon strongly suggests that it is best to investigate the dissociation of the perfect screw into two 30° partials, rather than the dissociation of the perfect 60° dislocation. This conclusion is based on several reasons listed below:

- the geometry of non-dissociated dislocation cores is better known for the screw dislocation than for the 60° dislocation;
- no 60° dislocation segments have been identified in experiments;
- the screw dislocation dissociation yields 30° partial dislocations only, for which a single core configuration is possible unlike the 90° partial;

- one intermediate step of the screw dissociation process has been revealed in a previous study [32].

In the following, I will then investigate the mechanisms leading to the dissociation of the screw dislocation. Figure 1 represents the different possible positions of a screw dislocation line in a $\{110\}$ plane. Stable screw dislocation configurations correspond to C_2 and A locations. In the first case, the screw can directly dissociate into two 30° partials located in the same $\{111\}$ slip plane (dashed lines in Fig. 1). In this work, I have focussed on this specific mechanism. In the second case, the A dislocation should first migrate from A to C_2 , along the $[101]$ direction (dotted line, Fig. 1). This path was investigated by Guérolé et al. using the EDIP potential [54]. They showed that the $A \rightarrow C_2$ core transformation could occur, thanks to a thermally activated mechanism, the activation energy being 2.31 eV, with little influence of stress. The C_2 screw configuration is then a stable intermediate step during the $A \rightarrow C_2 \rightarrow 30^\circ + 30^\circ$ transformation. Note that another possible transformation path could be $A \rightarrow B \rightarrow 30^\circ + 30^\circ$. Nevertheless, such a mechanism is likely to be more complicated than the one previously depicted, with a higher activation energy. In fact, a screw dislocation in B position is not stable and then could not be an intermediate step.

It is instructive to compare the core geometries of the 30° partial dislocation (see for instance Figs. 2a or 3b) with the C_2 screw dislocation (Figs. 3a or 4a). They are both characterized by the presence of dimers oriented along $[10\bar{1}]$ due to the reconstruction, leading to a similar core periodicity of $\sqrt{2}a_0$ along this orientation. The main difference is the presence of two lines of such dimers for the C_2 screw dislocation, arranged in a staggered pattern, while there is only one for the 30° partial dislocation. Then the C_2 dislocation core can be considered as the direct geometrical juxtaposition of two reconstructed 30° dislocations (with a $a_0/\sqrt{2}$ shift along $[10\bar{1}]$). Note that relaxing an initial configuration including two adjacent unreconstructed 30° dislocations yields a C_1 dislocation core instead.

Because of this similarity of core geometry, it is reasonable to expect that the mechanisms leading to the displacement of the 30° partial dislocation could be involved in the dissociation process as well. Then I have first investigated the migration of a single 30° partial dislocation with the simulation setup previously described. It is commonly agreed that dislocation displacement is associated with the formation of kink pairs followed by kinks' migration along the dislocation line [1]. Unfortunately, the issue lies in the complexity of possible kink configurations, especially when they are combined with reconstruction defects (see for instance [58] for a discussion about this point). Here, I have considered the four kink configurations

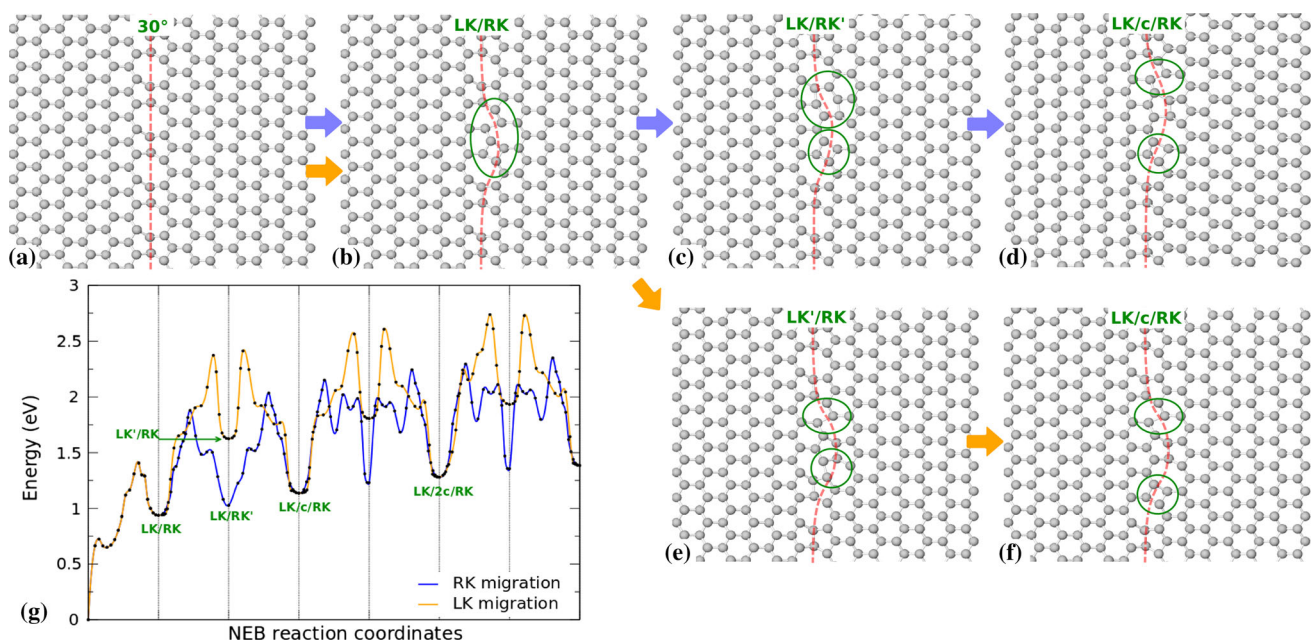


Fig. 2 a–f Atomistic configurations (slice along [111]) and g NEB calculated energies for kinks pair formation and migration in the case of a 30° partial dislocation. After the initial formation (a, b) of a pair of kinks (left, LK, and right, RK), the dislocation displacement occurs through the migration of RK (b–d, blue curve in g) or LK (b–e–f,

orange curve in g). LK' and RK' are intermediate configurations along the migration paths of LK and RK, respectively. c is the length of one translation unit along the reconstructed 30° partial dislocation core and is equal to $\sqrt{2}a_0$ (Color figure online)

usually reported in the literature [57], with the aim of (i) validating our setup and (ii) having elements of comparison for the C_2 screw dissociation.

Figure 2 shows the first steps of the 30° partial dislocation displacement, initiated by the formation of a pair of LK and RK kinks (Fig. 2b), and followed by the migration of either the RK kink (Fig. 2b–d) or the LK kink (Fig. 2b, e, f). The associated energy variations, calculated with the NEB technique, are reported in Fig. 2g. In agreement with previous investigations, RK' and LK' are intermediate configurations during the RK and LK kink migration, respectively. They are found to be energetically less stable than RK and LK, respectively. The structures of LK, LK', RK, and RK' kinks are in excellent agreement with those reported in the literature [57]. Note however that the NEB calculated energy variations in Fig. 2g appear to be more complex than those in earlier works (see for instance [56]), and include several minor inflection points or weakly stable minima. This is probably due to the large number of images in the present NEB calculations, and some might be non-physical. In fact, interatomic potentials based on complex mathematical expressions are more prone to yield such inflections in energy variations [60]. Nevertheless, the overall shape of the migration energy paths is in good agreement with previous works, and the most important point along the path, the one with the highest energy, does not depend on these inflections and minima.

The calculated barrier for the first step of the RK + LK kink pair formation is 1.41 eV. An alternative computed path leads to the formation of a stable RK' + LK' kink pair, with a greater activation energy of 2.33 eV. Increasing the separation between kinks, the energy variations tend to converge to a shape characteristic of a single kink migration. In Table 1, several formation and migration energies are reported, obtained by extrapolating the NEB results to large kink separations, and compared to earlier investigations. These energies are overall in good agreement with previous calculations, although it is difficult to understand why the kink formation values are closer to those obtained with the SW potential [56] or tight binding [57], than those obtained with EDIP in an earlier work [30].

C_2 screw dissociation

I now focus on the dissociation mechanism of the C_2 screw dislocation into two 30° partial dislocations. First, the energy difference between these two systems, with an increasing separation d between the partial dislocations, is calculated. The result is shown in Fig. 3, along with the corresponding atomistic configurations. d is computed as the average \hat{x} -position difference of the central core atoms of the 30° partial dislocations. d increases with steps of $\sqrt{6}a_0/4$, except for the initial step being approximately

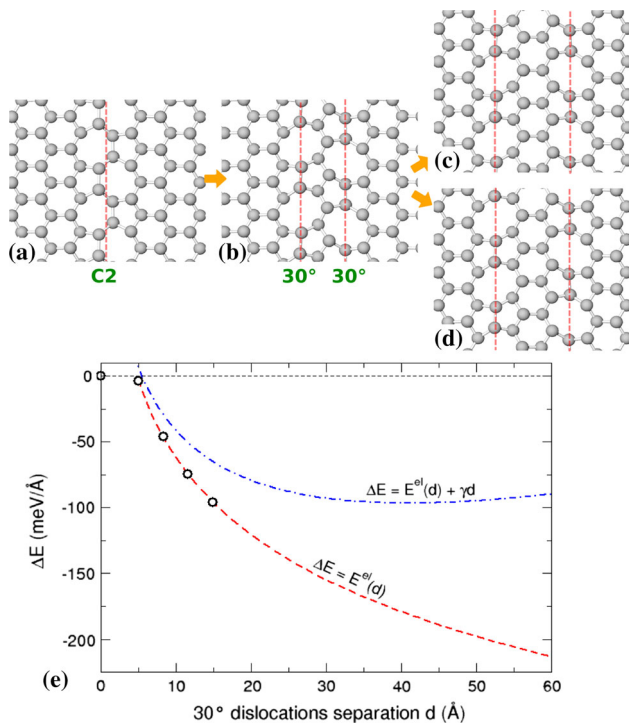


Fig. 3 **a–d** Stable configurations, from a whole C_2 screw dislocation (**a**) to two 30° partial dislocations with an increasing separation (**b–d**). **e** Energy difference, relative to the C_2 screw dislocation, as a function of the separation d . The red curve is a fit using the calculated energies (filled circles) and the expression 1. The blue curve shows the effect of adding the stacking fault energy contribution, missing in EDIP calculations, with a value $\gamma = 33 \text{ mJ/m}^2$ [59] (Color figure online)

$3\sqrt{6}a_0/8$. It appears that there is an energy gain even for the shortest separation. This is in agreement with a similar calculation performed in diamond, albeit with a different screw core configuration [61]. In Fig. 3, one can see that there are two different configurations for $d = 5\sqrt{6}a_0/8$ (and larger separations with the period $\sqrt{6}a_0/2$). In one case, the dimer lines in the two 30° cores are aligned along $[10\bar{1}]$ (Fig. 3c), whereas they are shifted by $a_0/\sqrt{2}$ along the same direction (Fig. 3d). A negligible energy difference between these two configurations was calculated in all cases.

According to elasticity theory and assuming isotropy, the energy variation for larger separations should follow the interaction energy between two dislocations [1], i.e.,

$$E^{el} = -\frac{\mu}{2\pi} \left[(\mathbf{b}_1 \cdot \boldsymbol{\zeta})(\mathbf{b}_2 \cdot \boldsymbol{\zeta}) + \frac{(\mathbf{b}_1 \times \boldsymbol{\zeta})(\mathbf{b}_2 \times \boldsymbol{\zeta})}{1 - \nu} \right] \ln\left(\frac{d}{r_0}\right). \tag{1}$$

Consequently, the calculated energy variations for $d \neq 0$ is fitted with the expression $\Delta E = E^{el} = \alpha \ln d/\beta$, the two parameters α and β being the elastic factor and the core radius, respectively. The best fit is obtained with

$\alpha = 84 \text{ meV/\AA}$ and $\beta = 4.81 \text{ \AA}$ (Fig. 3). Note that the dissociation of the screw dislocation is accompanied by the creation of an intrinsic stacking fault bordered by the 30° partial dislocations. The energy penalty associated with the stacking fault expansion leads to a restoring force, which opposes to the repulsive interaction between partial dislocations. This effect is not present in our calculations since the stacking fault energy is zero when calculated with EDIP, as it is often the case with short-ranged bond order interatomic potentials. A corrected energy variation is represented in Fig. 3, simply obtained by adding γd (blue curve), with $\gamma = 33 \text{ mJ/m}^2$ determined using first-principles calculations [59]. With this correction, the dissociation width is predicted to be 4 nm in good agreement with experiments.

As expected, the previous calculation indicates that the screw dislocation dissociation is energetically favored, even for the shortest separation. But the energy barriers associated to the lattice friction hindering the motion of the 30° partial dislocations are missing. NEB calculations have then been performed to determine the minimum energy paths associated with the formation and migration of kinks leading to the first dissociation steps. Considering the structural similarities between C_2 and 30° cores, configurations including stable kinks similar to those obtained for the 30° dislocation displacement have been used as endpoints in NEB calculations. The final minimum energy paths and the associated energy variations are represented in Fig. 4. The computed mechanisms lead to the dissociation of the C_2 screw dislocation by the formation of an LK + RK kink pair first, followed by the migration of one or the other kink along the dislocation line.

Starting with the initial step, it is found that the stable kink pair LK + RK is structurally close to the LK + RK kink pair obtained in the case of a single 30° partial dislocation (Figs. 2b, 4b). But its formation energy is lower (0.52 eV compared to 0.94 eV). The formation path is similar for both cases. Nevertheless, the corresponding energy barrier is 2.14 eV for the C_2 dissociation, i.e., substantially higher than the value of 1.41 eV for the single 30° partial dislocation. I also considered the formation of an LK' + RK' pair as a first dissociation step. In that case, the computed formation energy of 1.42 eV is much larger than that for the LK + RK pair, although the associated energy barrier of 2.37 eV is comparable. The computed migration mechanisms of LK and RK (Fig. 4b–f) are also similar to those obtained in the case of the single 30° partial dislocation. Both LK' and RK' are stable intermediate configurations along the LK and RK displacement, and migration energies are about 1.4 and 1.3 eV, respectively. The LK value is the same as for the single 30° partial dislocation, while the RK value is slightly higher.

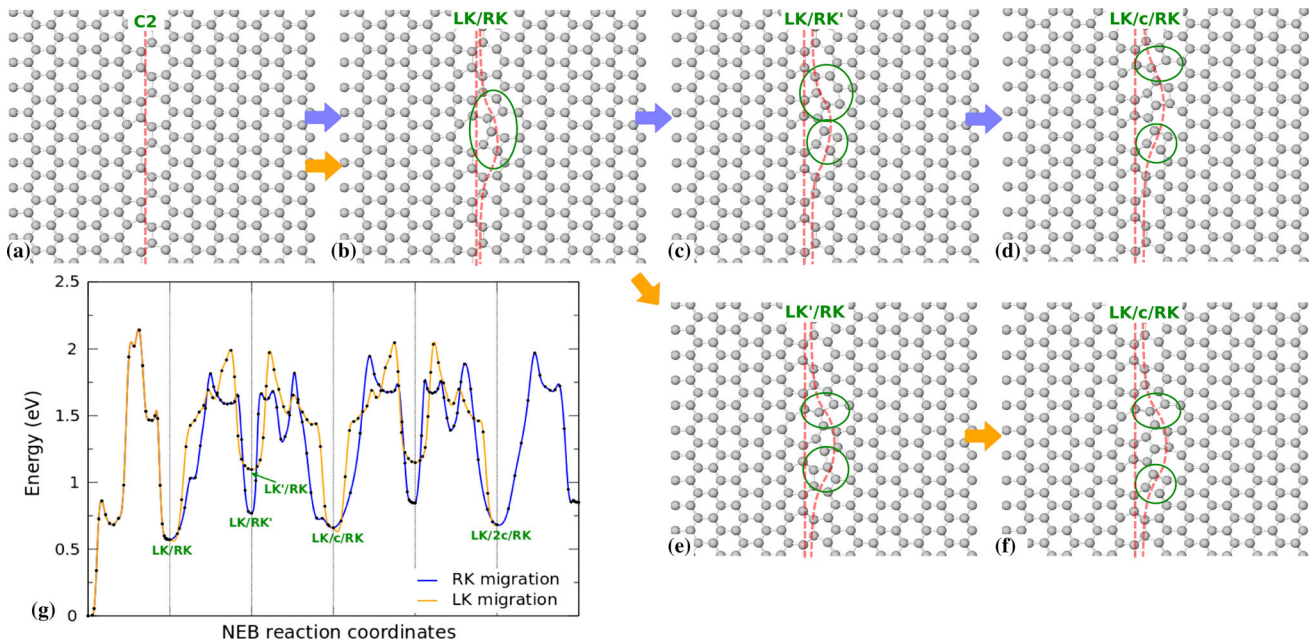


Fig. 4 a–f Atomistic configurations (slice along [111]) and (g) NEB calculated energies for kink pair formation and migration associated to the first dissociation steps of a C₂ screw dislocation. After the initial formation (a, b) of a pair of kinks (left, LK, and right, RK), the dislocation displacement occurs through the migration of RK (b–d, blue

curve in g) or LK (b–e–f, orange curve in g). LK' and RK' are intermediate configurations along the migration paths of LK and RK, respectively. *c* is the length of one translation unit along the reconstructed C₂ screw dislocation core, and is equal to $\sqrt{2}a_0$ (Color figure online)

Table 1 Kink formation (F_k) and migration (W_m) energies (in eV), computed in this work (first column) and from earlier numerical simulations using the same potential (EDIP [30]), the Stillinger–Weber (SW) potential [56], and tight binding [57].

	EDIP	EDIP [30]	SW [56]	TB [57]
$F_k(\text{LK} + \text{RK})$	1.6	1.37	1.63	1.57
$F_k(\text{LK}' + \text{RK}')$	2.2	1.88	2.13	2.61
$W_m(\text{LK} \rightarrow \text{LK}')$	1.4	1.46	0.82	1.52
$W_m(\text{LK}' \rightarrow \text{LK})$	0.8	0.84	0.4	1.09
$W_m(\text{RK} \rightarrow \text{RK}')$	1.0	1.22	0.74	2.03
$W_m(\text{RK}' \rightarrow \text{RK})$	1.0	0.89	0.82	1.62

Overall, it is observed that the first steps leading to the dissociation of the C₂ dislocation are comparable to those leading to the displacement of a single 30° partial dislocation. I already mentioned that it is not surprising given the related structures of the two initial configurations. According to this result, only the first dissociation steps were investigated, for one should quickly recover the behavior of a single 30° partial dislocation for larger separations *d*. The most important conclusion here is that it is the formation of the initial stable LK + RK kink pair which requires the highest energy activation during the C₂ screw dissociation. This first step is then the limiting process, with an activation energy of 2.14 eV.

Summary

The calculations reported here have lead to the following conclusions:

- the dissociation of a C₂ screw dislocation into two 30° partial dislocations occurs by the formation of kink pairs, followed by the migration of one or the other kink along the dislocation line;
- these kinks are structurally very close to kinks associated with the displacement of a single 30° partial dislocation, even for the first dissociation step;
- the activation energy for the whole dissociation mechanism is 2.14 eV.

The second point above can be explained by the strong similarity between the C₂ screw and 30° partial cores. Nevertheless, one may argue that these kinks are obtained mainly because they were initially introduced as stable mid-points for NEB calculations. Additional calculations have then been performed for determining other stable configurations, in particular for the first dissociation step. Those yield alternative solutions, but a structural analysis revealed that they are combination of kinks and core reconstruction defects (LC and RC, following the notations in [57]) and that large energy barriers have to be overcome for their formation. Therefore, it is reasonable to conclude that the mechanism described in the previous sections is most likely to dissociate the screw dislocation.

Considering now the activation energy of 2.14 eV, it is interesting to notice that it is slightly lower than the activation energy associated with the screw dislocation core transformation $A \rightarrow C_2$ (2.3 eV [32], calculated with the same potential). Then, if this core transformation is thermally activated, the screw dissociation should also take place. The activation energies in the range of 2.1–2.3 eV are relatively large, suggesting that temperatures as high as about 900 K are required for these processes to occur in an experiment. Godet et al. have shown that at these temperatures there is a change in the nature of nucleated dislocations [62]. It is then difficult to discriminate between dissociation and nucleation, and both could be responsible for the observed transition in experiments [19, 20, 27].

The dissociation of dislocations in annealing experiments has been observed at 600 K [21]. The activation energies calculated in this work then appear slightly too high. One possible cause is the overestimation of these energies using EDIP. The effect of stress also has not been considered here and might help lower the reported activation energies. In fact, a recent molecular dynamics study by Li and Picu revealed that screw dislocation dissociation could be favored in the presence of a specific stress state [28]. This might explain contradicting experimental results, as well as the existence of two transition temperatures [21].

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Compliance with ethical standards

Conflict of Interest The author declares that he has no conflict of interest.

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